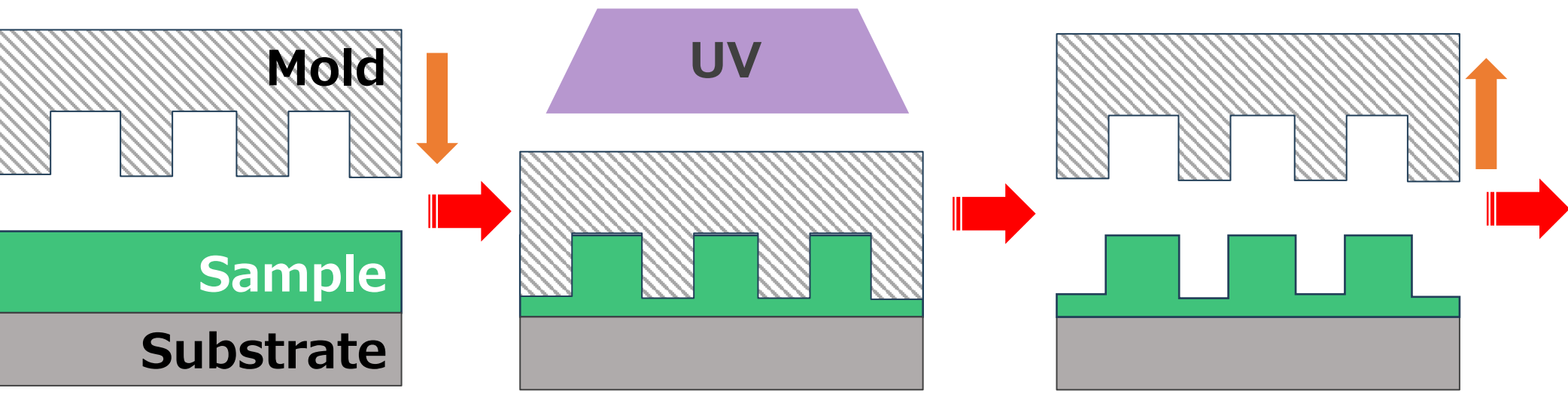


Plasma Etching Resistant UV Nanoimprint Materials

■ Product Overview

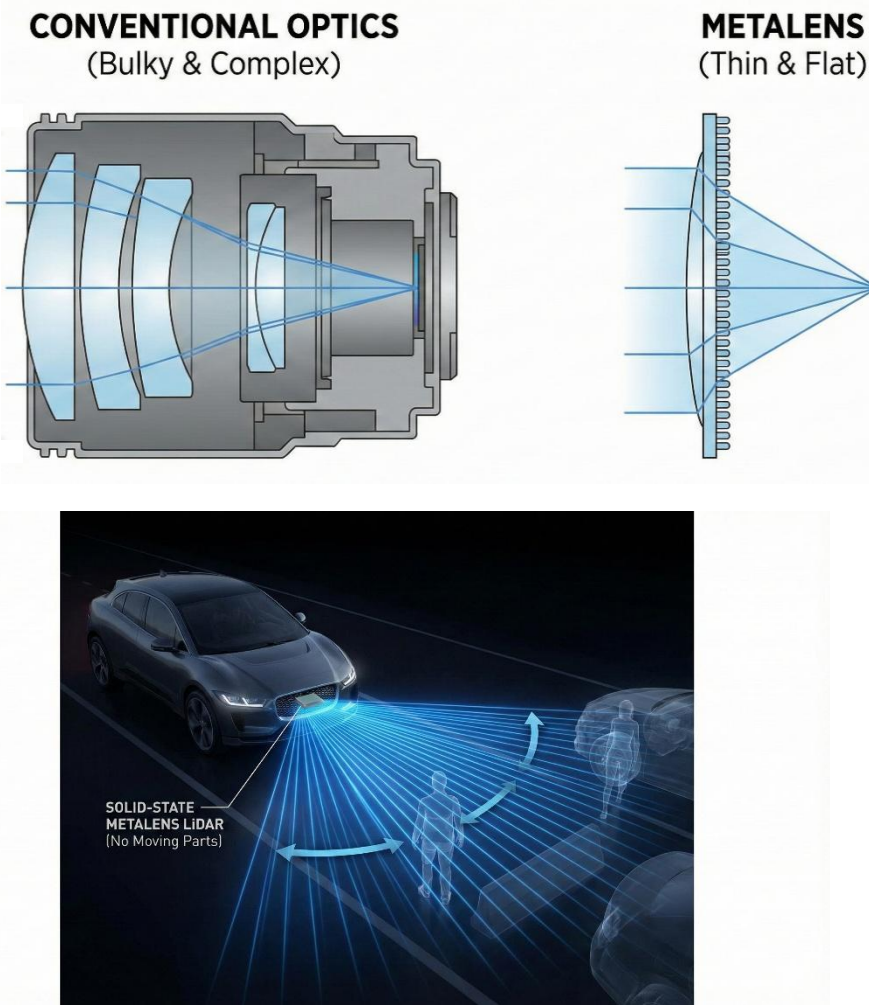
- **Nano-scale Precision:** Achieves high-fidelity imprinting at the nanometer order
- **Excellent Adhesion:** Enables primer-less adhesion to inorganic substrates such as glass and silicon wafers
- **Superior Etching Resistance:** Offers higher resistance compared to glass

<Nanoimprint Process>

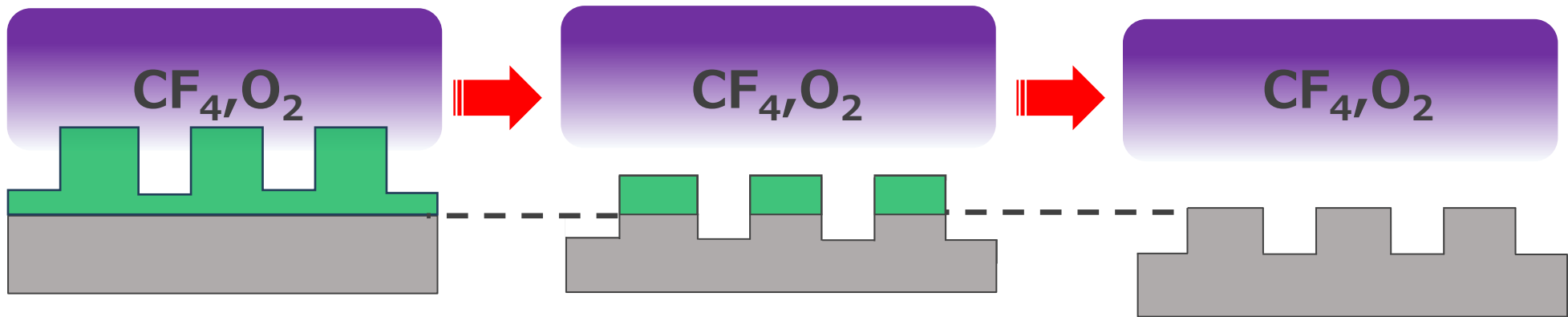


■ Target Applications

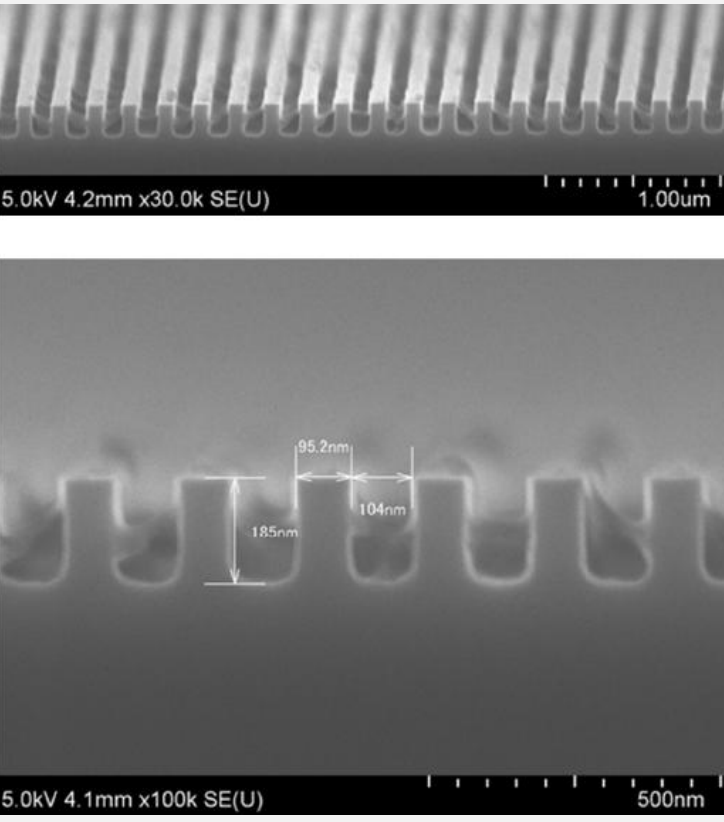
- **Metallenses** (Thin & Flat optical components)
- **DOE** (Diffractive Optical Elements)
- **Moth-eye Structures**
- **Replica Molds**



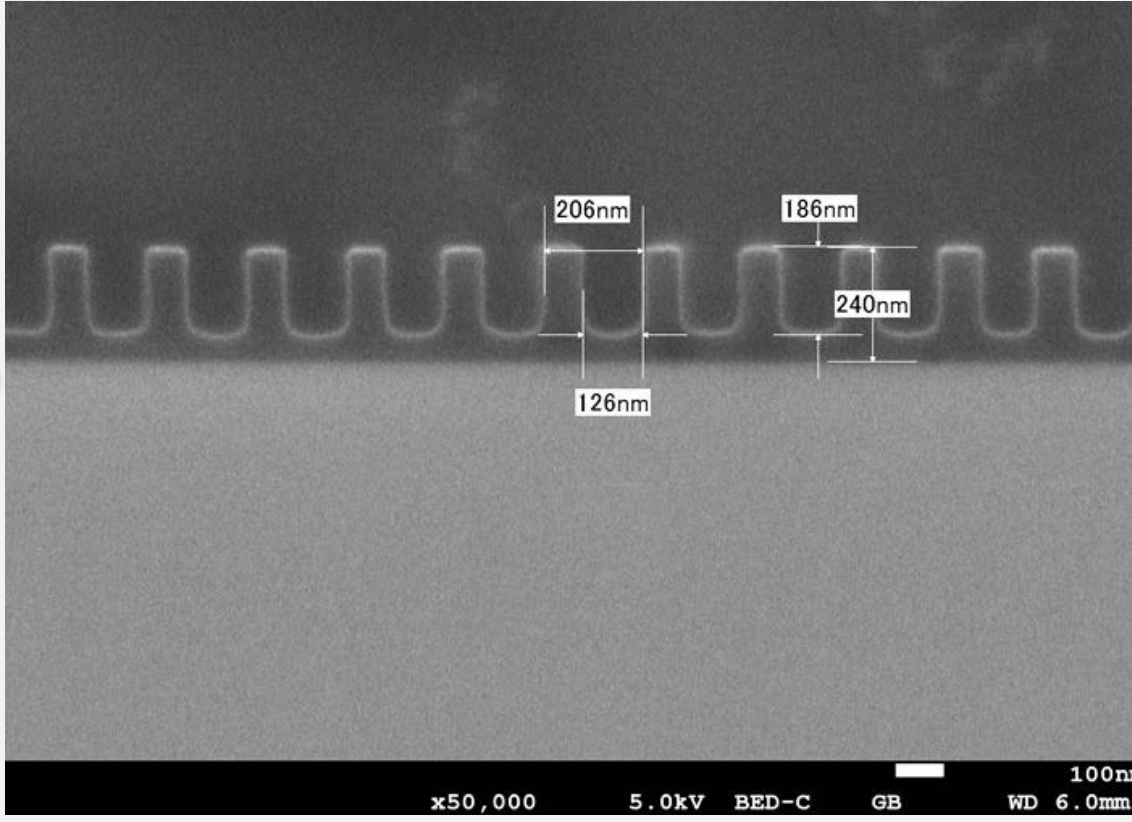
<RIE Process>



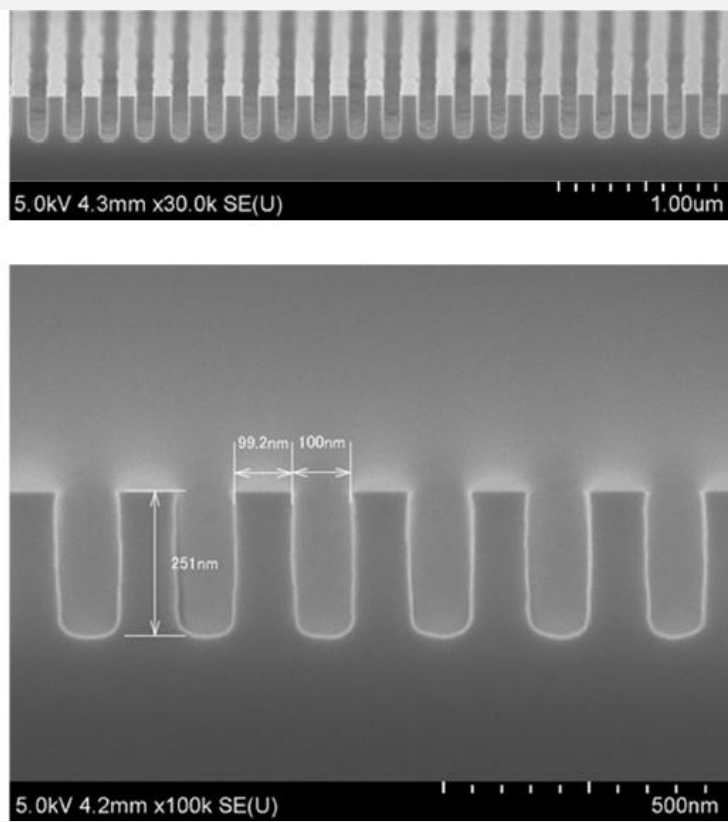
Si Mold
Depth 200nm/Width100nm



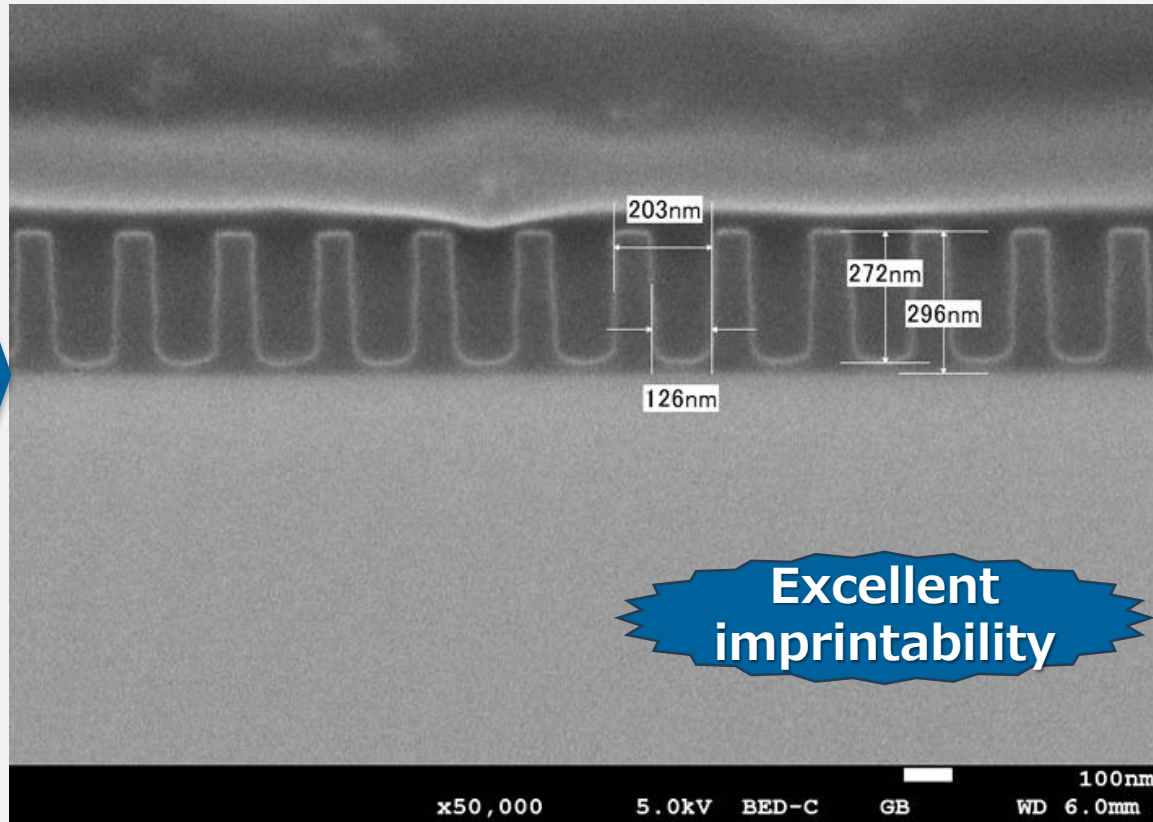
Imprinted resin structure



Si Mold
Depth 300nm/Width100nm



Imprinted resin structure

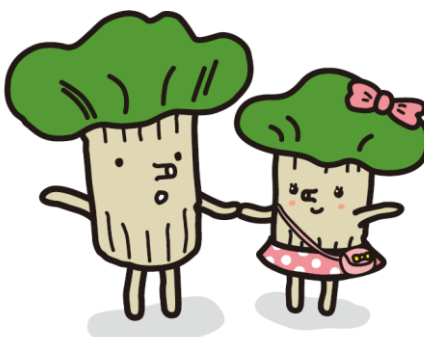
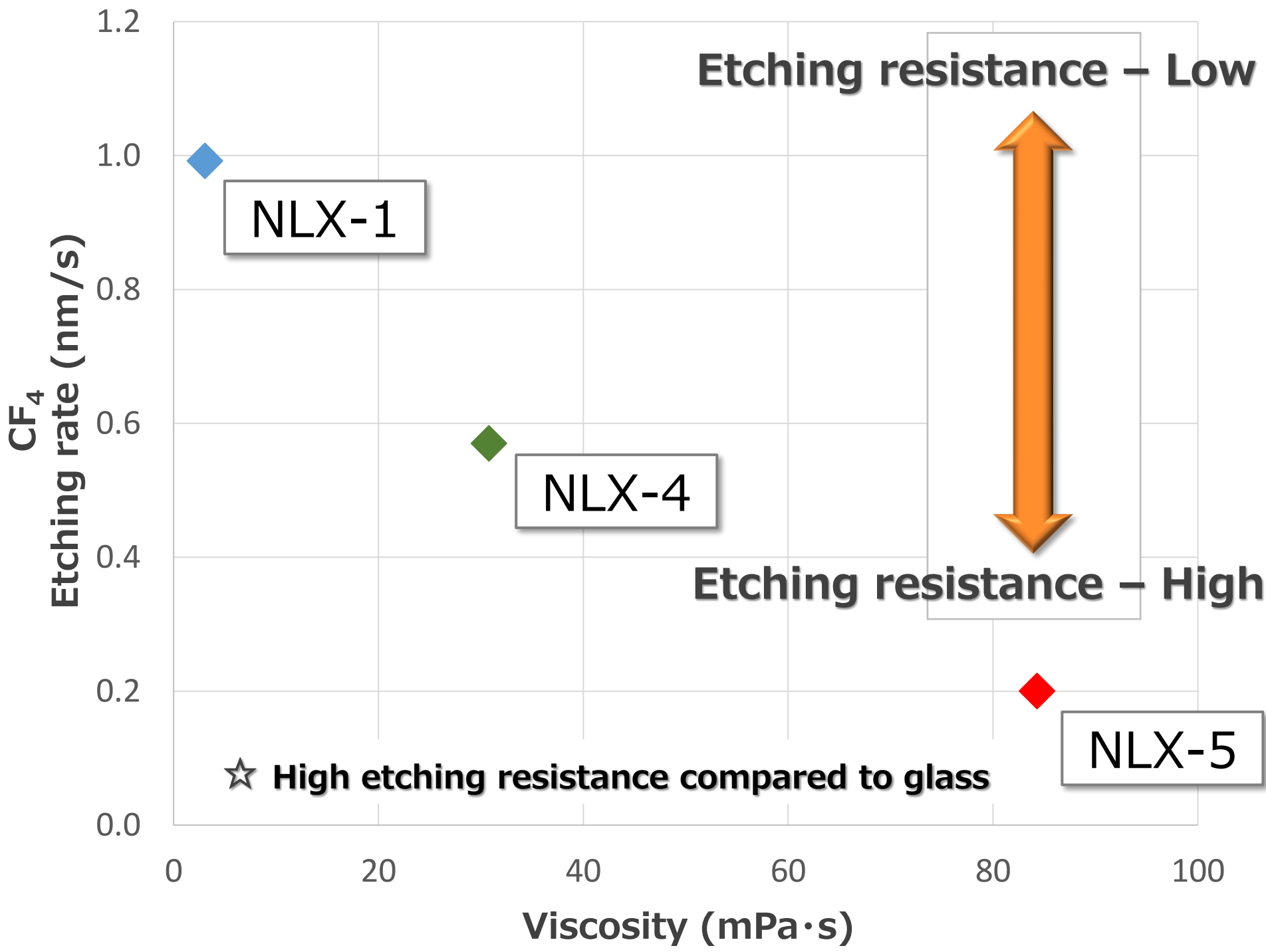


■ Technical Specifications

Sample		NLX-1	NLX-4	NLX-5
Features		Low Viscosity	Low Viscosity/ Etching Resistance	High Etching Resistance
Solid Content		50%	60%	60%
Solvent		PGMEA	PGMEA	PGMEA
Viscosity (mPa·s)	Liquid	3	5	7
	After Drying	15	30	85
Etching Rate (nm/sec)	CF ₄	1.0	0.6	0.2
Adhesion	Glass	○	○	○
	Si Wafer	○	○	○

*For comparison, the SiO₂ etching rate is 1.2 nm/sec

☆ PFAS-free versions available



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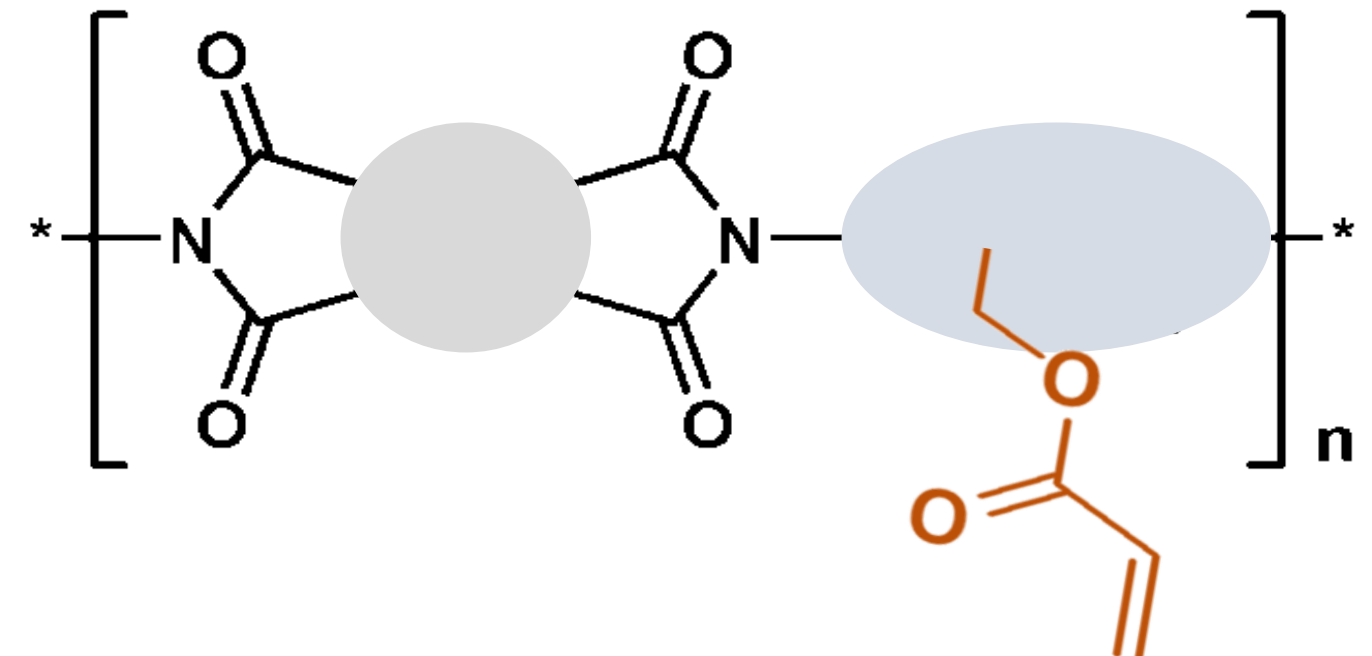


Photosensitive Polyimide Composition "PR-P4"

■ Product Overview

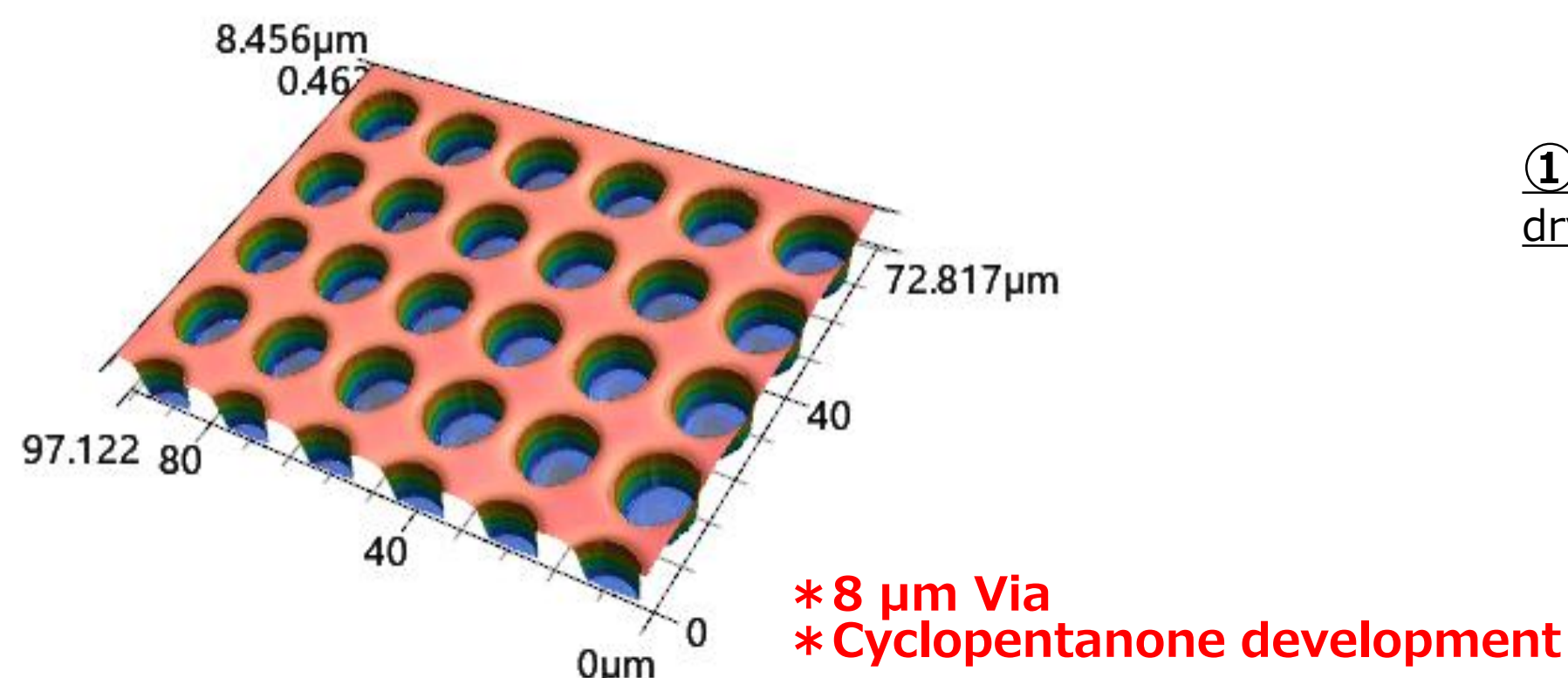
PR-P4 is a high-performance photosensitive polyimide material that balances **high heat resistance** and **high transparency**

- **Polyimide-derived Performance** : Offers excellent toughness, heat resistance and a low CTE
- **Process Efficiency**: The material is pre-imidized, eliminating the need for imidization
- **Fine Patterning**: Enables high-resolution patterning via UV irradiation and solvent development



UV-reactive group

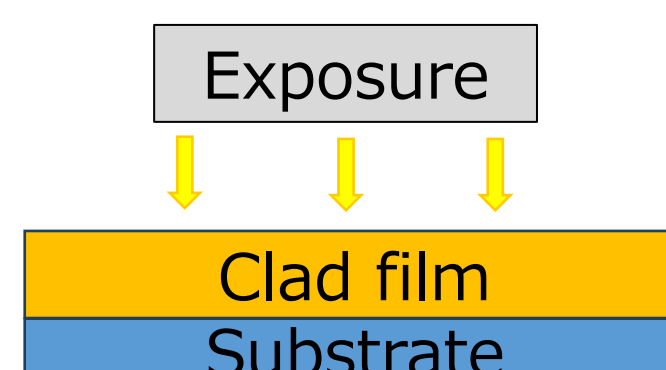
<Patterning Example>



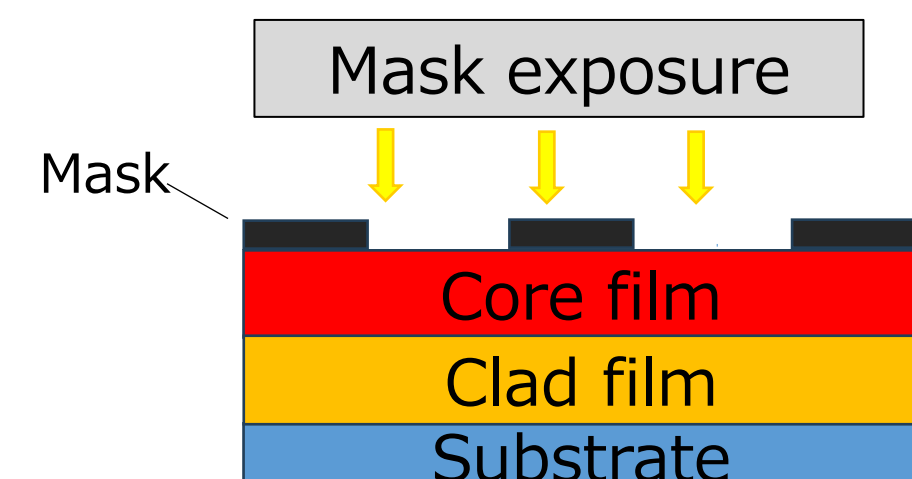
<Capable of forming optical waveguides>

Schematic diagram of optical waveguide fabrication

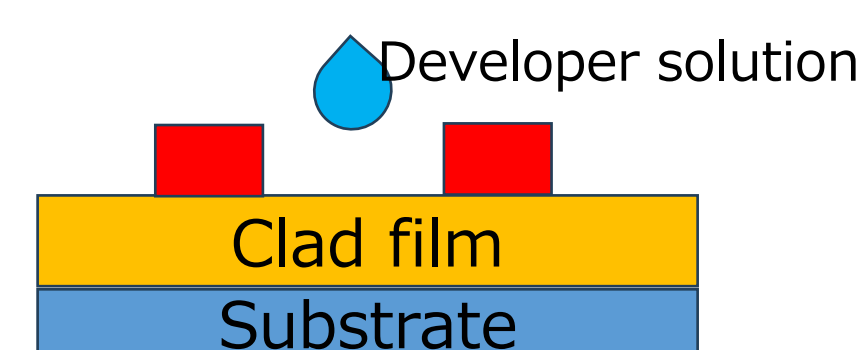
① **Clad Lamination**: Laminate the clad dry film onto the substrate and expose.



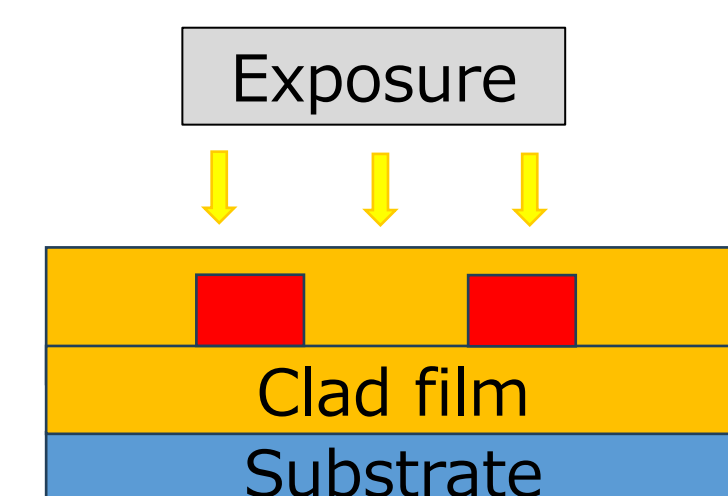
② **Core Lamination**: Laminate the core film and perform mask exposure.



③ **Development**: Develop the core to create the waveguide pattern.



④ **Final Cladding**: Laminate the top cladding layer via thermocompression and perform final UV curing.



Cross-section of an optical waveguide

■ Target Applications

- **Optical Waveguides** (Core and Cladding materials)
- **Resist Materials** for semiconductor back-end processes
- **High Heat-Resistant Films**
- **Hollow Sealing Materials** for MEMS devices

Simultaneous achievement of high heat resistance and high transparency

■ Technical Specifications

PR-P4		Remarks
Liquid Property		
Solvents	Dimethylacetamide / Methylcyclohexane	-
Solid Content	Approx. 30%	Design value
Viscosity	400 mPa·s	E-type (@25°C)
Photoinitiator	Contained	-
Cured Film Properties		
Solvent Developability	○	Cyclopentanone (8μmVia)
Storage Modulus (GPa)	30°C	2.7
	175°C	1.4
CTE (ppm/°C)	70	DMA
5% Weight Loss Temperature (°C)	370	TMA
Elongation at break (%)	8	TG-DTA
Shrinkage Rate (%)	8	Tensilon
Transparency 850nm	99.5%	CLSM (Dry to After-bake)
		Initial & After 230°C×120min

* Note: The values provided are representative and not guaranteed specifications

Substrate: Alkali-free glass or Release paper
Thickness: 10μm
Drying: 115°C for 5 minutes
UV Curing: 600 mJ/cm² (UV-A, ghi-line)
Post-Exposure Bake: 200°C for 60 minutes



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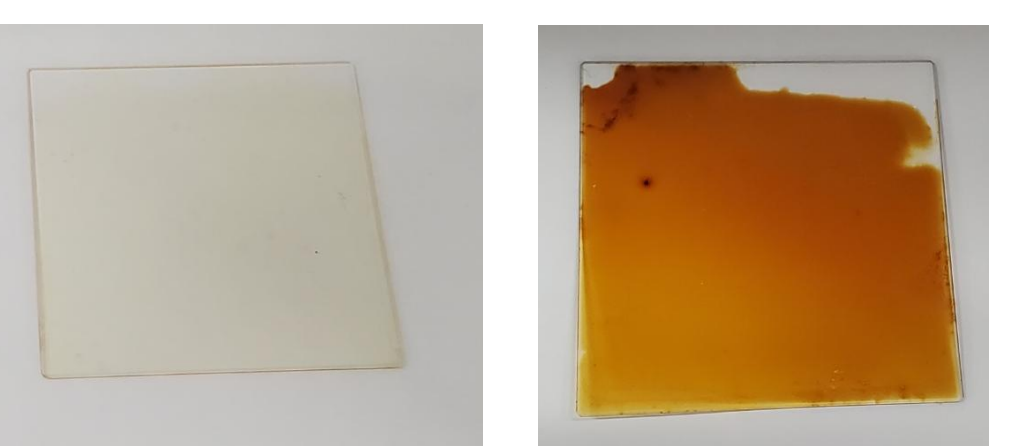
<Liquid and Cured Film Appearance>



Liquid Appearance



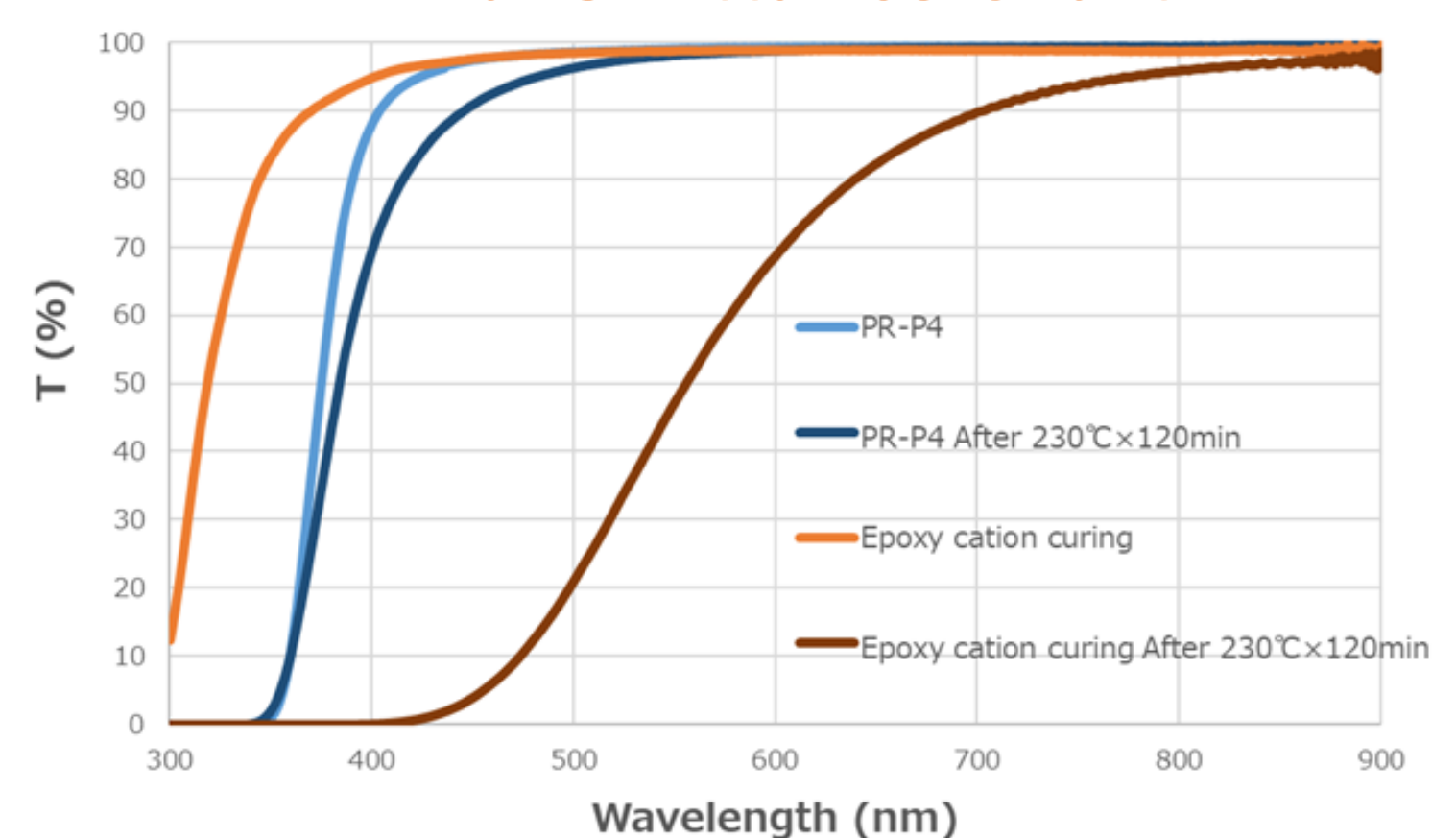
After UV Curing



After 230°C×120min

Comparison Sample
Epoxy cation curing
After 230°C×120min

< Transmittance Chart >

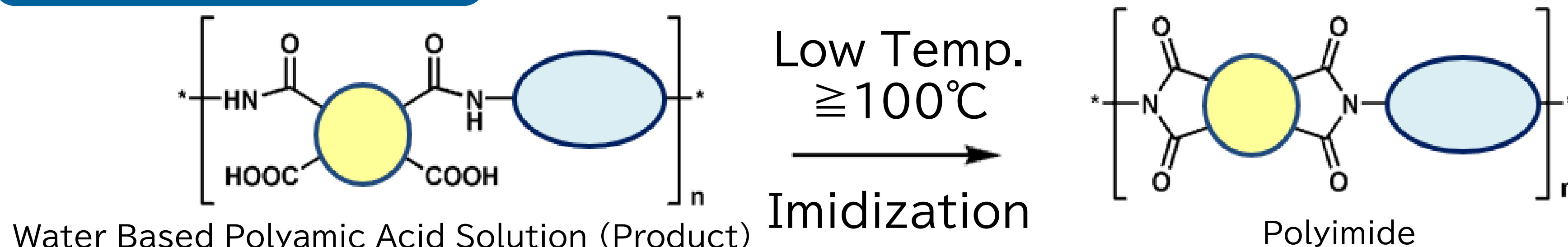


☆ High transmittance even after heating



Water Based Polyamic acid solutions

Features



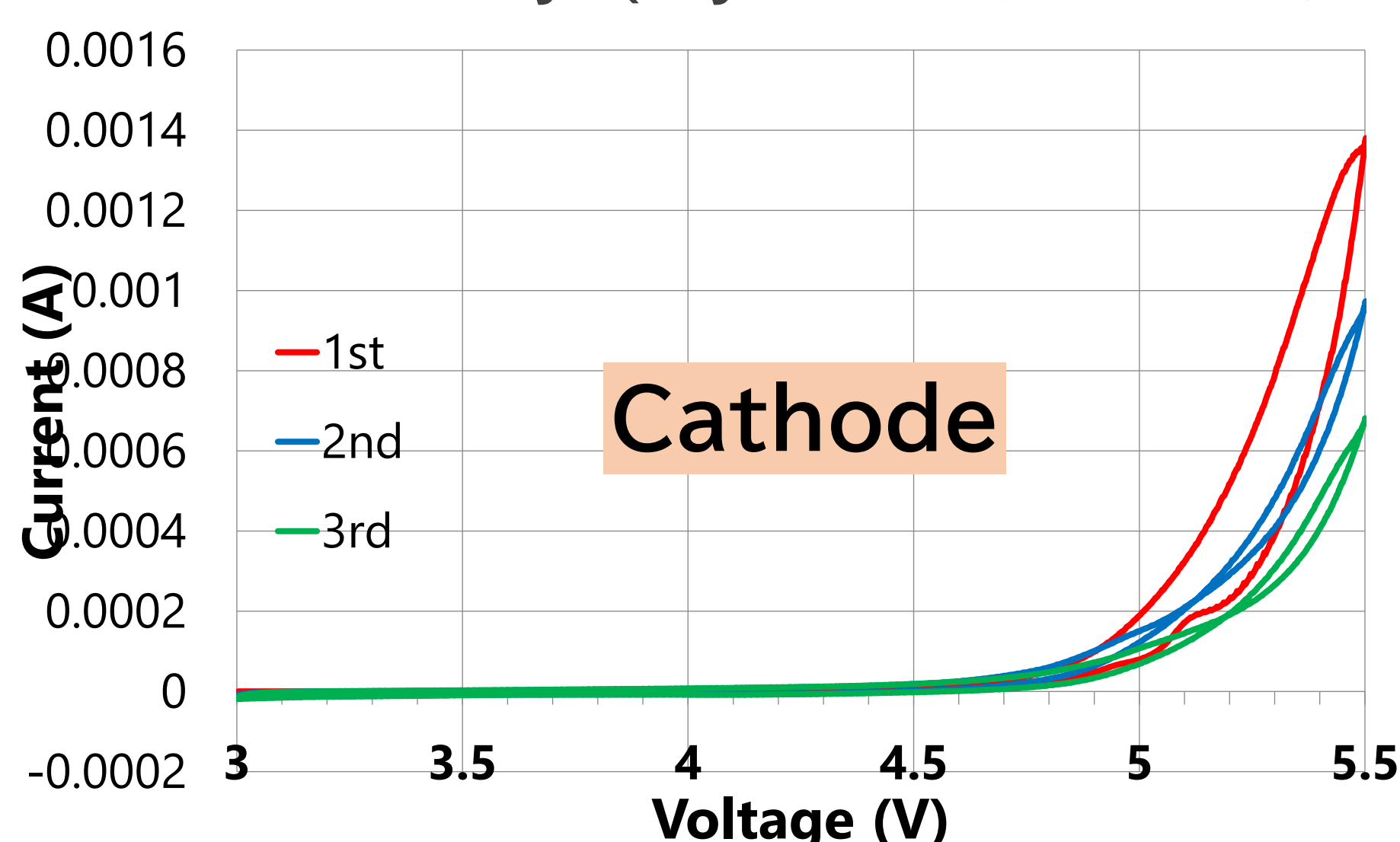
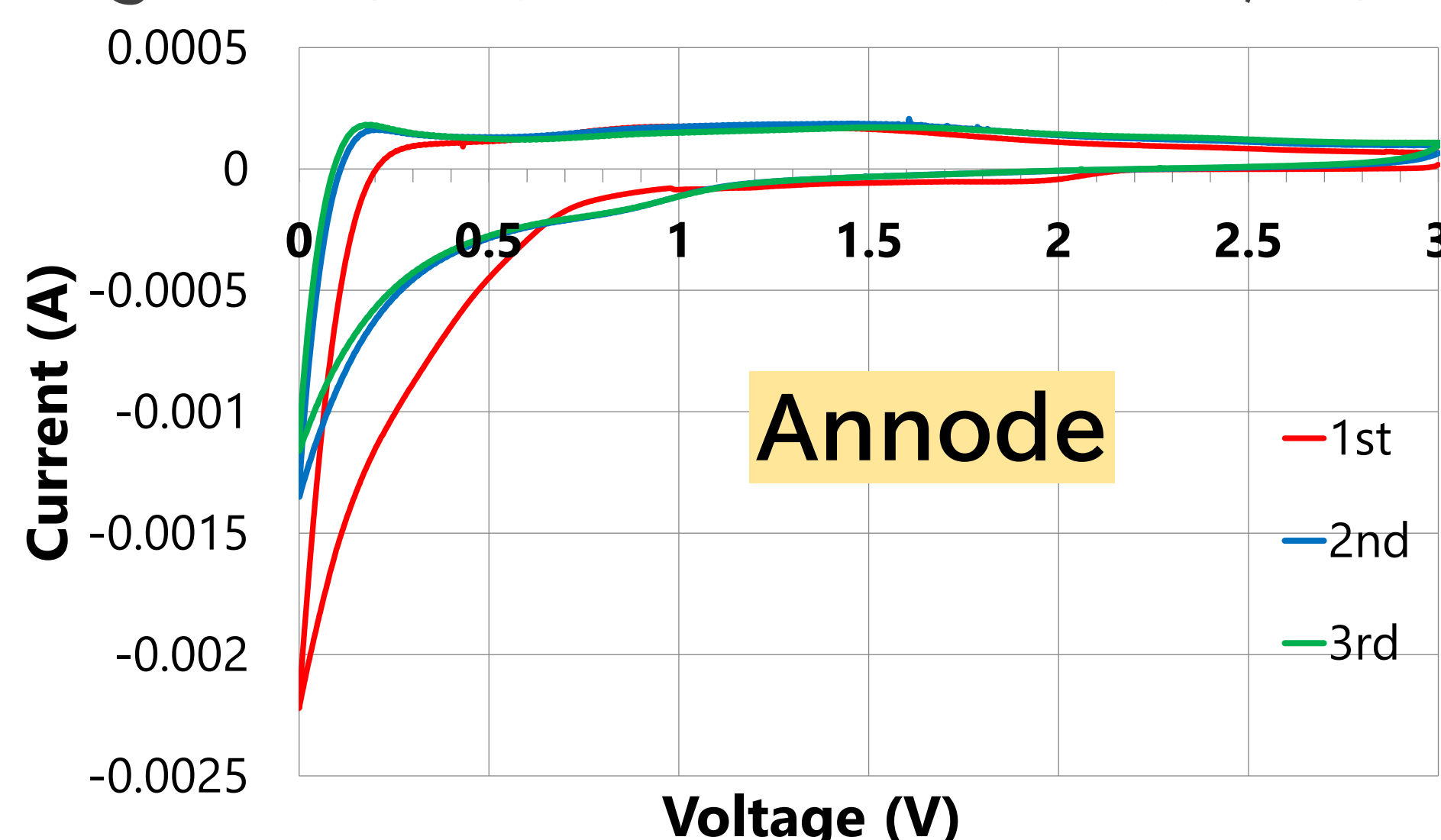
- Water soluble resin PFAS free⇒Ecofriendly
- Low Temp. Cure($\geq 100^\circ\text{C}$)
- High Thermal stability($T_g: 130 \sim 320$)
- High Chemical & Oxidation/Reduction stability
- High strength resin ○High Breakdown Voltage($> 300\text{kV/mm}$)
- Good dispersibility(Si, SiC, SiO, Graphite, CNT...



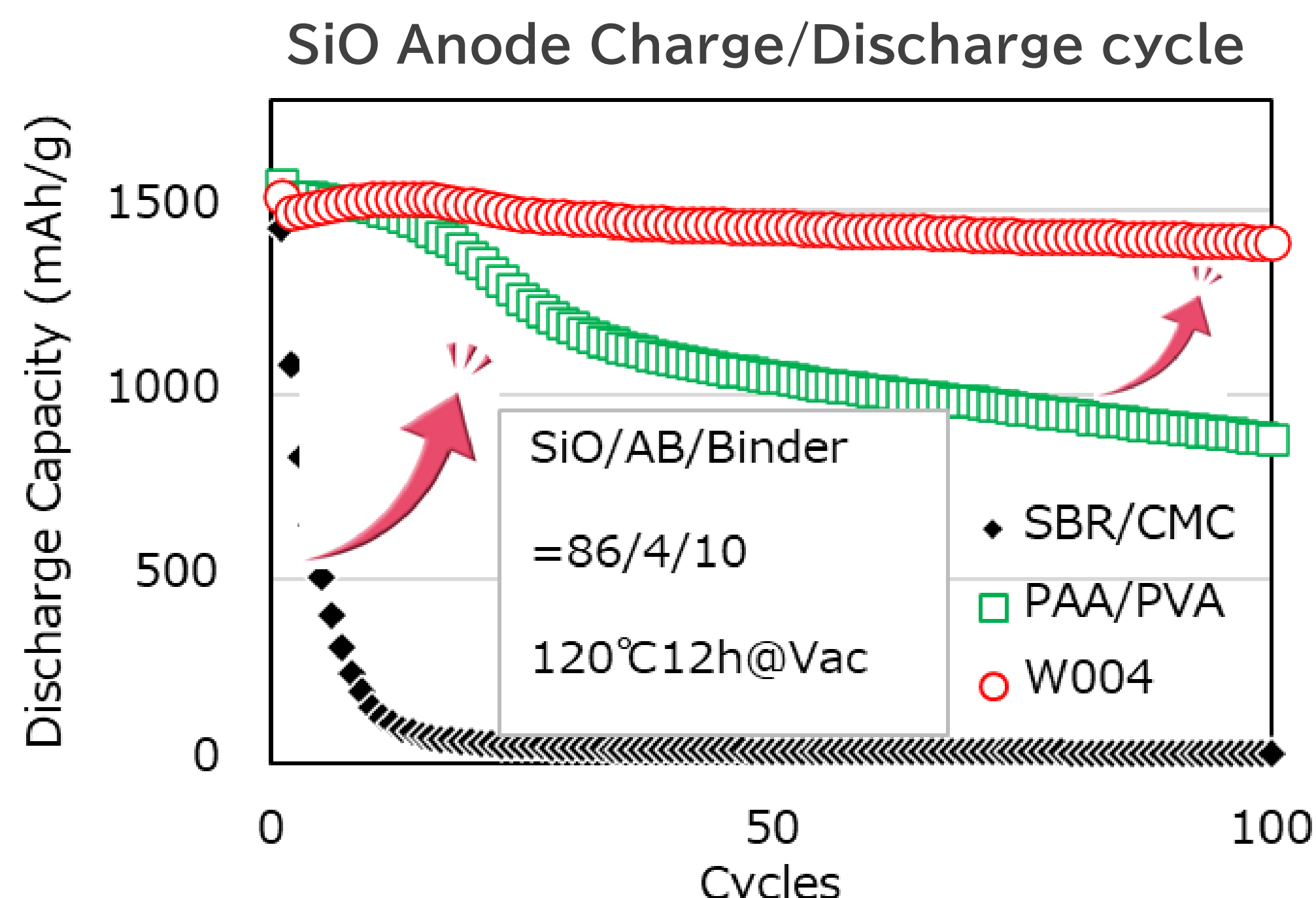
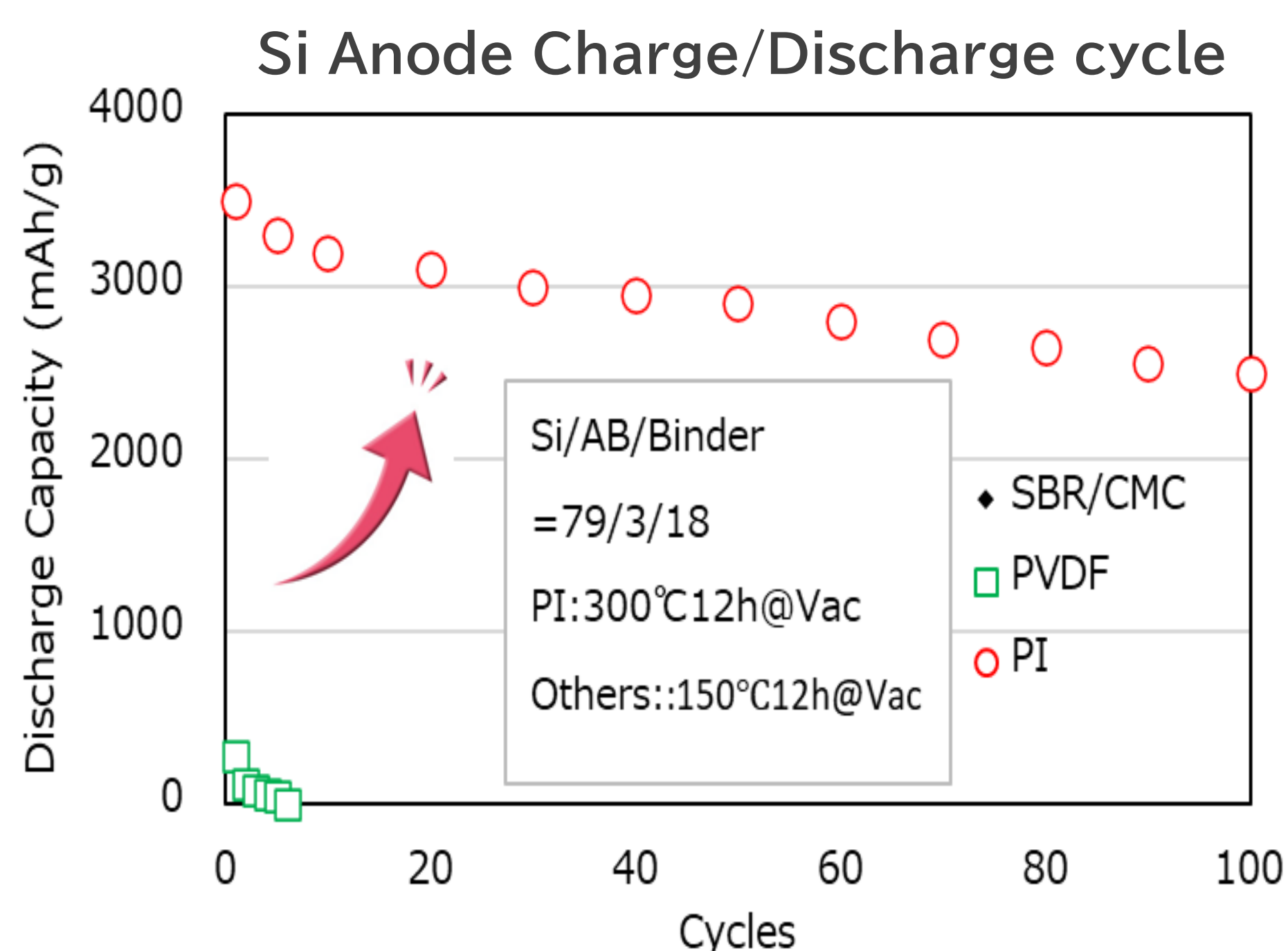
Appearance

Oxidation/Reduction stability

High Chemical and Oxidation/Reduction stability (Cyclic voltammetry)



Battery Performance(Half Cell evaluation)



Varnish properties

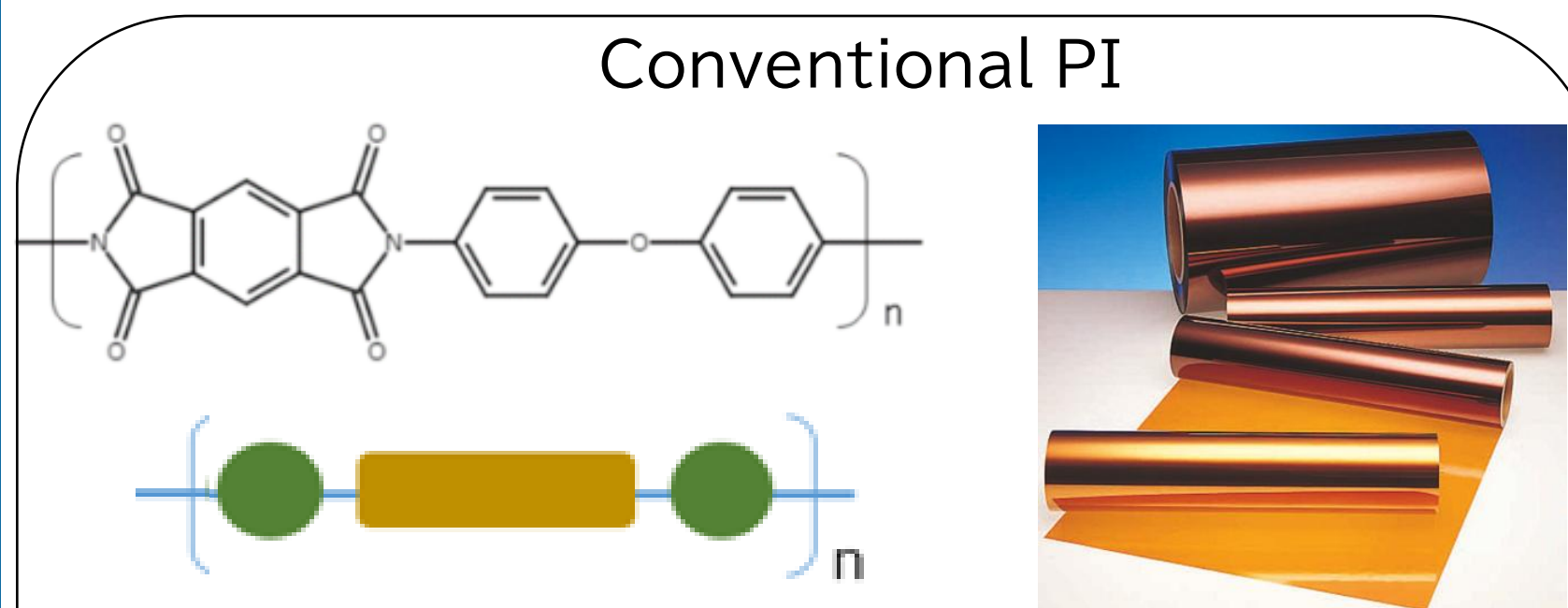
Film properties

Non volatile (%)	Viscosity (Pa·s)	pH	Modulus (GPa)	Elongation (%)	T _g (°C)	Breakdown Voltage(kV/mm)
20-40	1-10	7-10	1-5	10-150	130-320	300-400

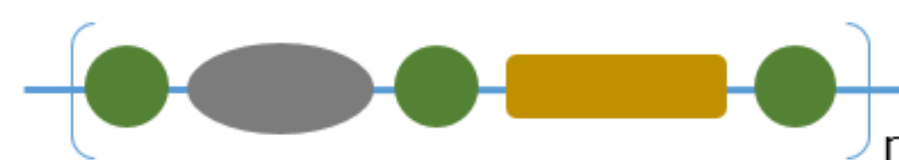


Thermoplastic solvent-soluble Polyimide resin solution

Features



Thermoplastic solvent-soluble Polyimide resin solution : Hard and soft moiety



- Biomass material
- Good processability (Process Temp.: $<180^{\circ}\text{C}$)
- Low water adsorption ($<0.5\%$)
- Low Dielectric constant (2.7)
- Low Dissipation tangent (0.002) → For various application
- Good adhesion / Heat resistance



Product

After Dry

● : Imide ○ : Aliphatic (soft) ■ : Aromatic (hard)

Application

Material

Low Dk/Df
Polyimide resin
「PIAD」



- + Cross-linkers, Curing agents
- + Filler
- + Additives, etc..

Adhesives for high-frequency substrates

→ Low dielectric, High heat resistance, High adhesion, High reliability

- Flexible Copper Clad Laminates
- Bonding Sheets (BS)
- Coverlay (CVL)
- Resin Coated Copper foil (RCC)

Binders for Lithium-ion batteries

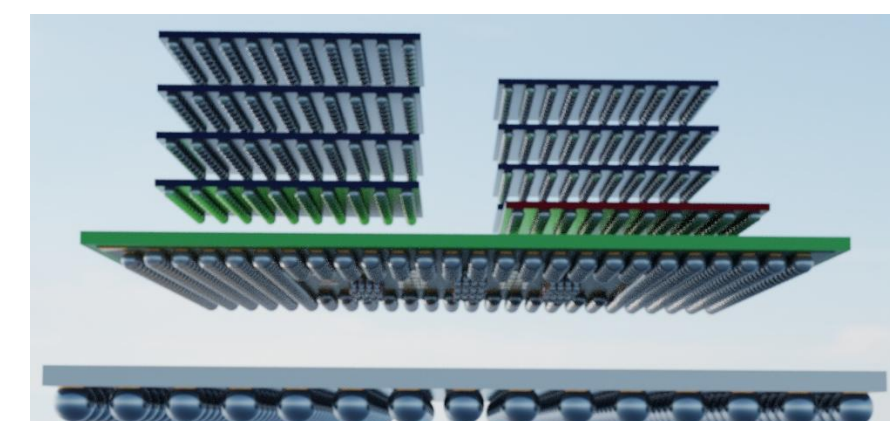
→ High reliability, water-based, Low temperature curing

- Binders for electrode
- All solid state Battery
- Separator coating (Heat resistant @ 200°C)
- Insulation coating (Edge coating)

Resins for semiconductor back-end processes

Light curable, thermo-curable
→ Low dielectric constant, Low elasticity, Low water absorption

- Resins for Redistribution layer (RDL)



FPCs



Cover lay



Bonding sheet

Main boards, Package substrates



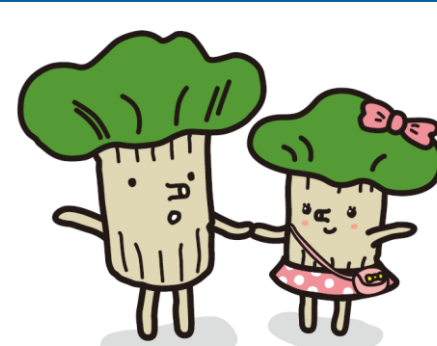
Resin coated copper



Interlayer insulating film

Property (Varnish & Film)

試験項目		Unit	150L	300	13000	152H	252	605
Varnish	Main solvent	-	Cyclohexanone			Toluene		NMP
	Viscosity	mPa·s/25℃	400	600	4000	3000	700	8000
	Non volatile	wt %	29	30	20	42	33	26
Film	Maximum Stress	MPa	10.7	13.5	95	17.5	35.1	80
	Fracture Elongation	%GL	100 <	2.5	13	100 <	13.7	10
	Elastic Modulus	GPa	0.41	0.73	1.9	0.53	0.63	1.5
	Water absorption rate	%	0.2	0.4	-	0.1	0.2	0.3
	Dk@10GHz	-	2.6	2.7	3.0	2.5	2.6	2.7
	Df@10GHz	-	0.0023	0.0024	0.0055	0.0016	0.0017	0.0026
	Softening point	C deg.	80 / -	140 / -	- / 240	80 / -	100 / -	180 / 130
	Breakdown Voltage	kV/mm	52	47	-	45	45	73



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Pine Power to Fight Sliminess

Organic-based Biomass Anti-biofilm Agent

Features

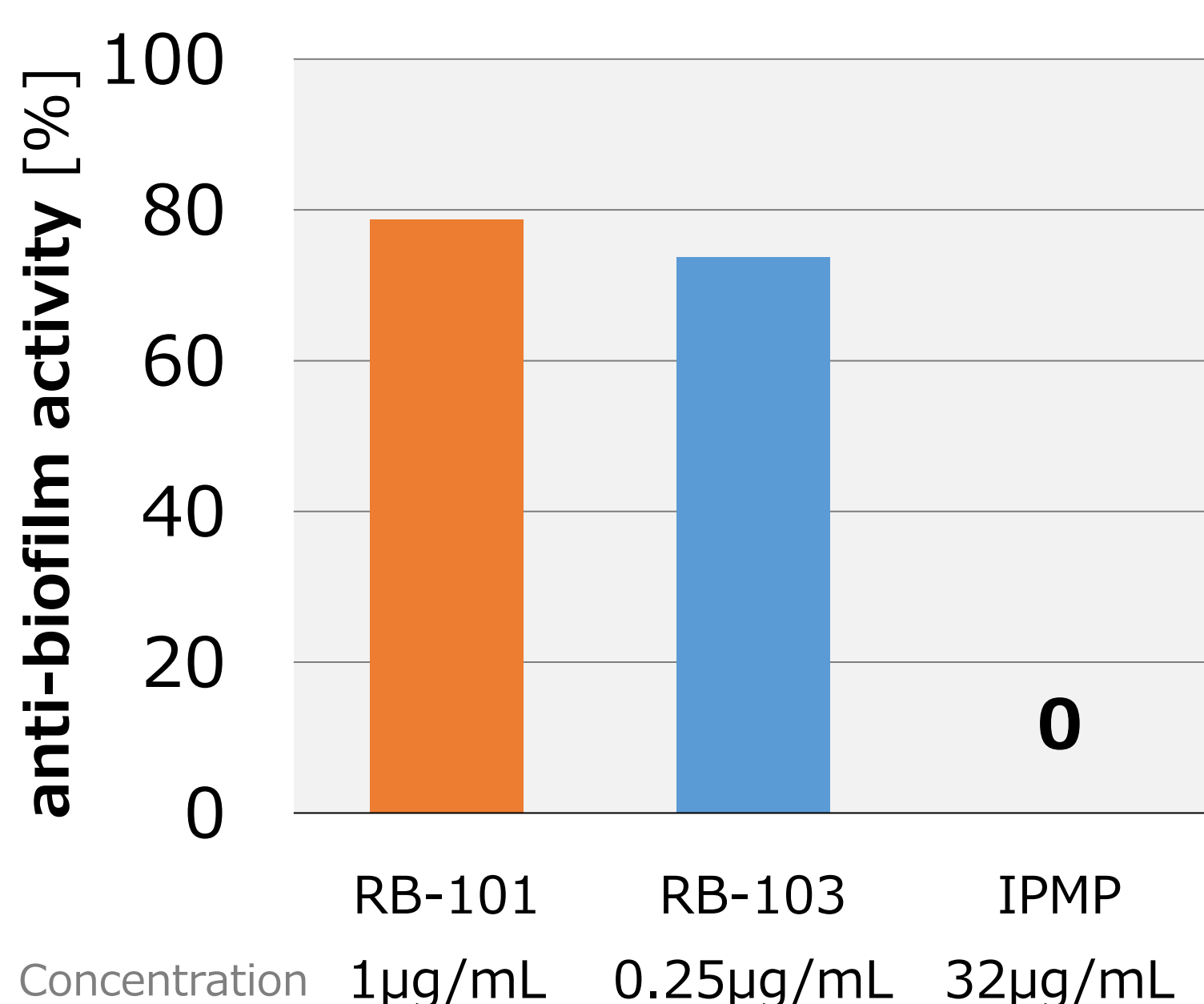
Under Development



- ✓ Natural Materials (pine trees)
- ✓ High antibacterial and anti-biofilm activity
- ✓ Various Sample Forms
(Plastics / Ink / Coating / Spray / Emulsion)

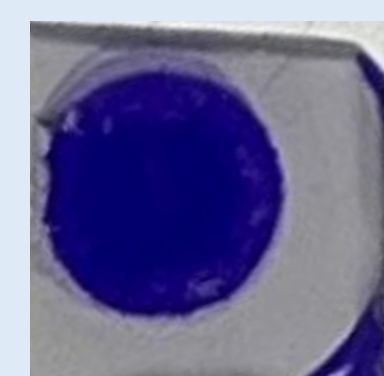
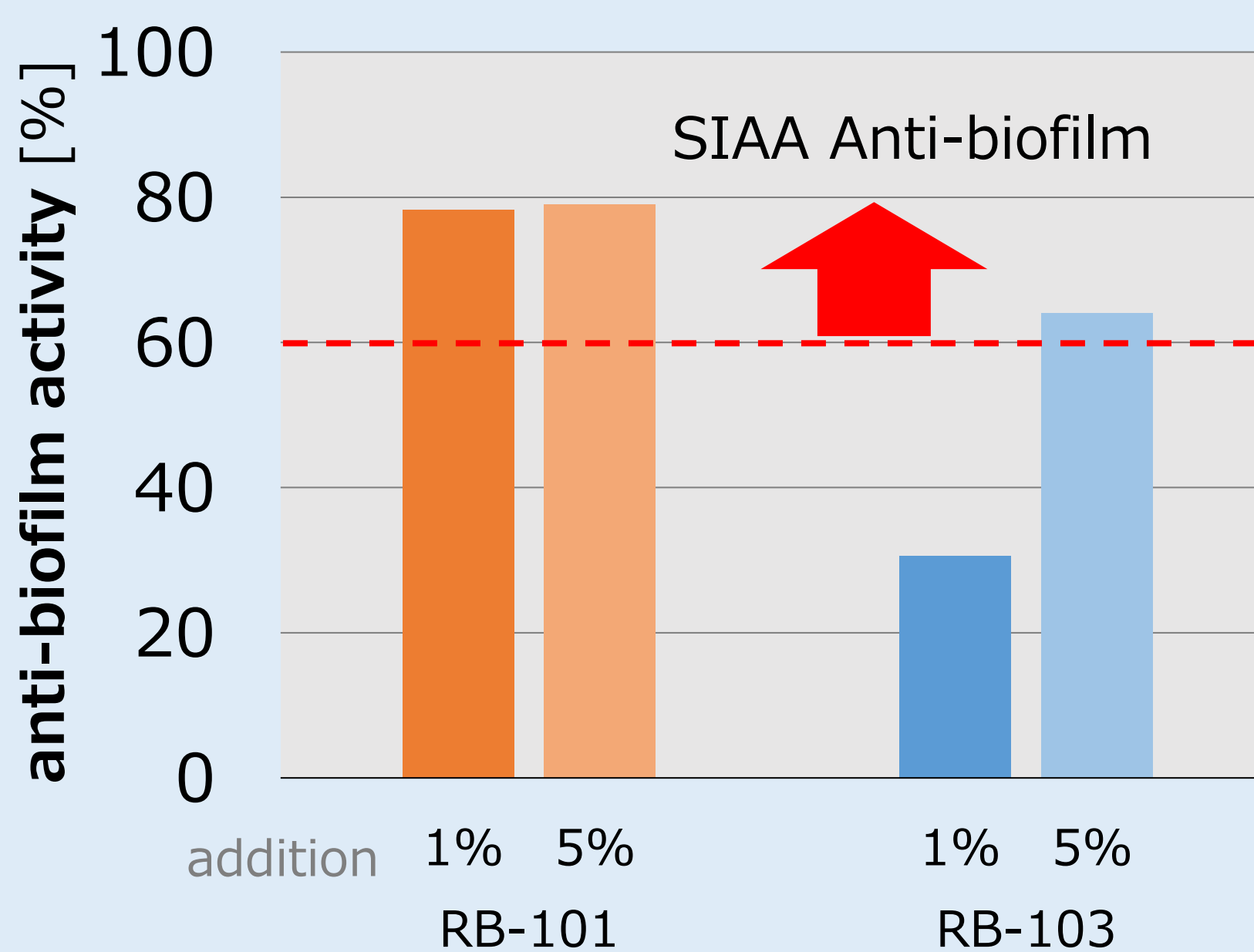
◆ Anti-biofilm

S. mutans, 1/4 concentration of MIC

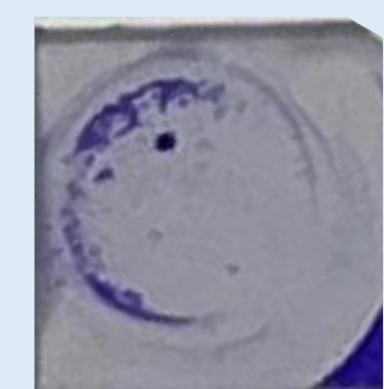


◆ Anti-biofilm (Knead into PP)

Similar conditions to ISO4768



Not added

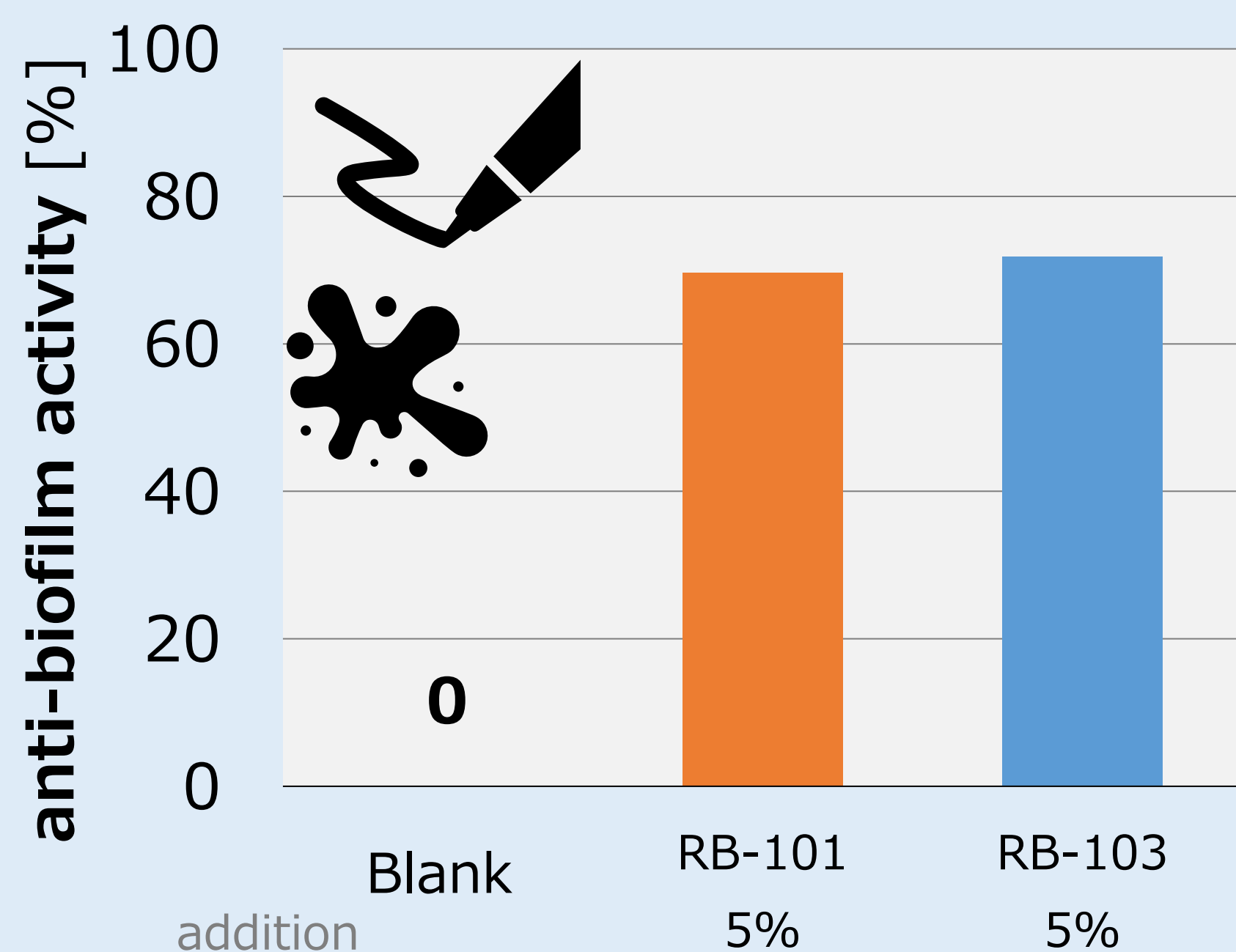


RB-101

80% inhibition of biofilm

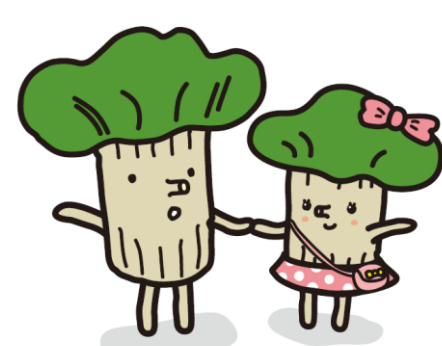
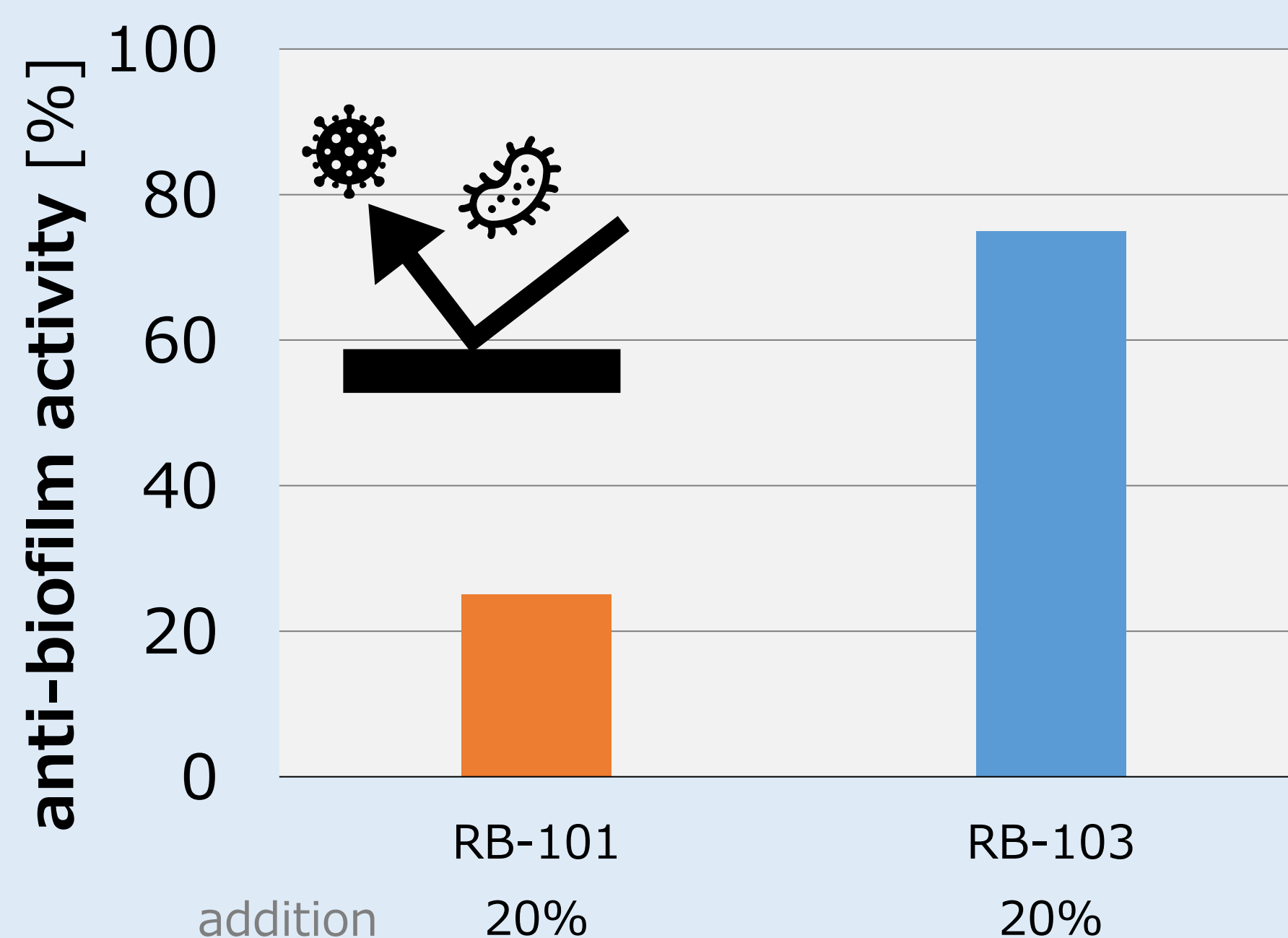
◆ Anti-biofilm (added to ink)

Added to acrylic-based ink, applied to film after
Similar conditions to ISO4768



◆ Anti-biofilm (added to coating)

Added to UV coating agent, applied to film
After UV curing, similar conditions to ISO4768



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Dissimilar Materials Adhesion Enhancer

New Product 「Rosin polyol」

Features

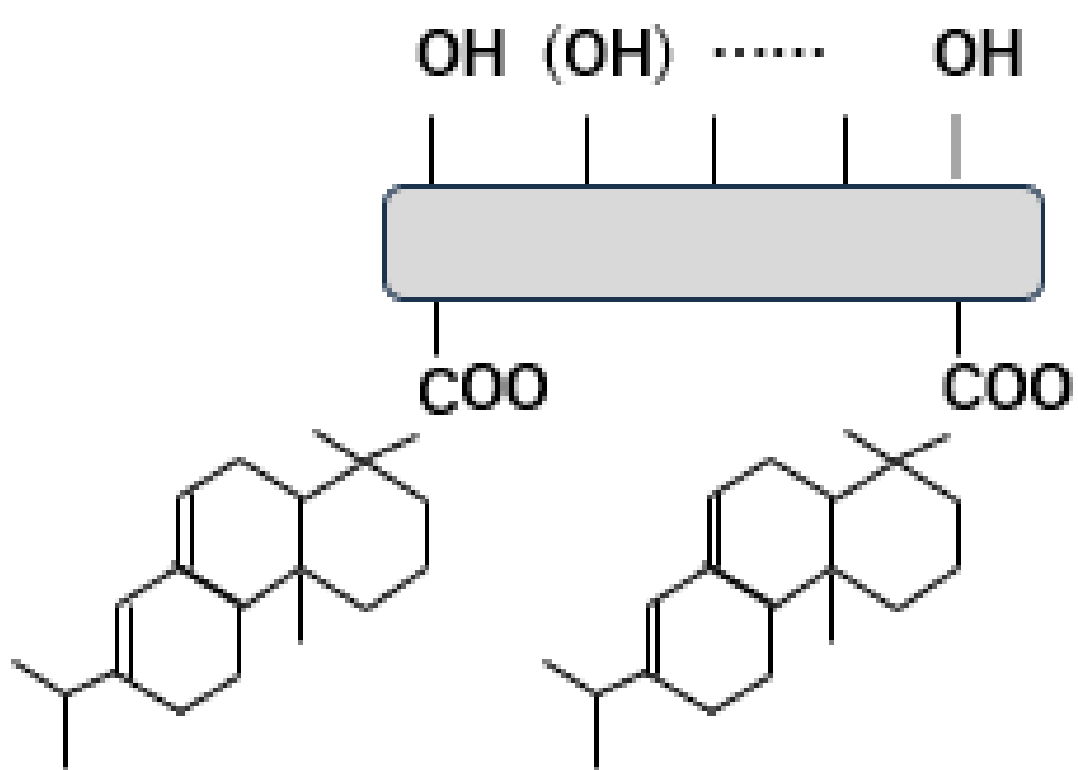
- ✓ Improved adhesion to difficult-to-bond materials
- ✓ Enhanced formability through reduced material viscosity
- ✓ Increased interfacial strength between dissimilar materials (resin/filler)

◆Product properties

	D-6021	D-6011
Softening point (°C)	100	90
Acid value (mgKOH/g)	<1	<1
Hydroxyl value (mgKOH/g)	160	125
Molecular weight (Mw)	2000	800
Td5 (°C)	380	360

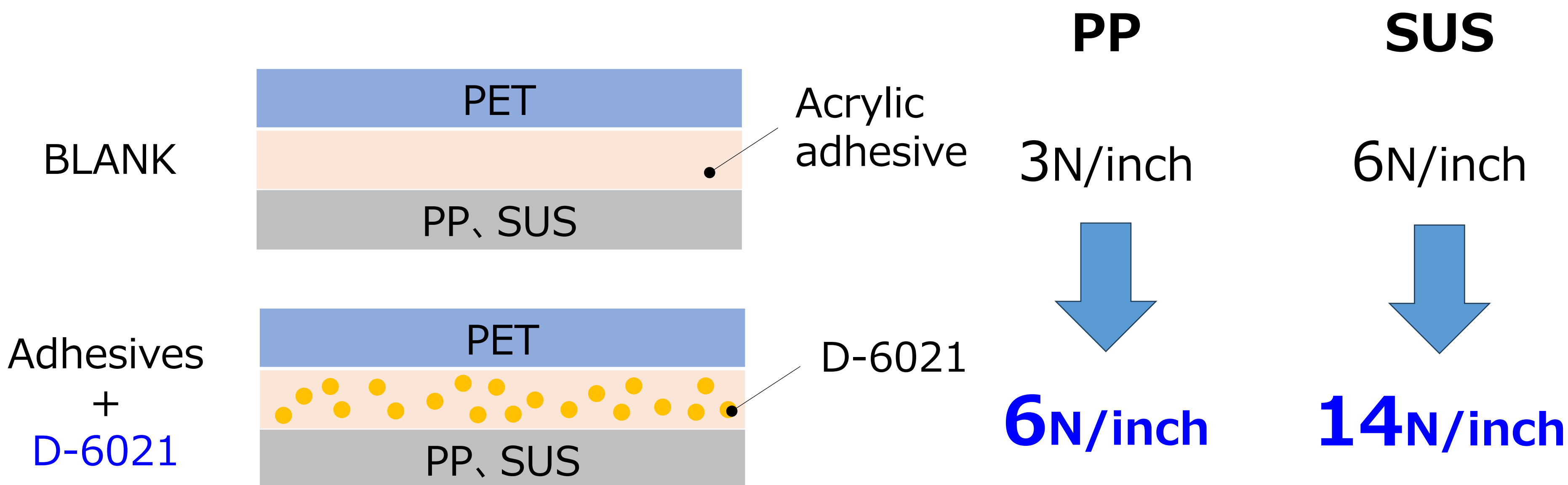
Structure

(D-6011 : OH group at only terminal)

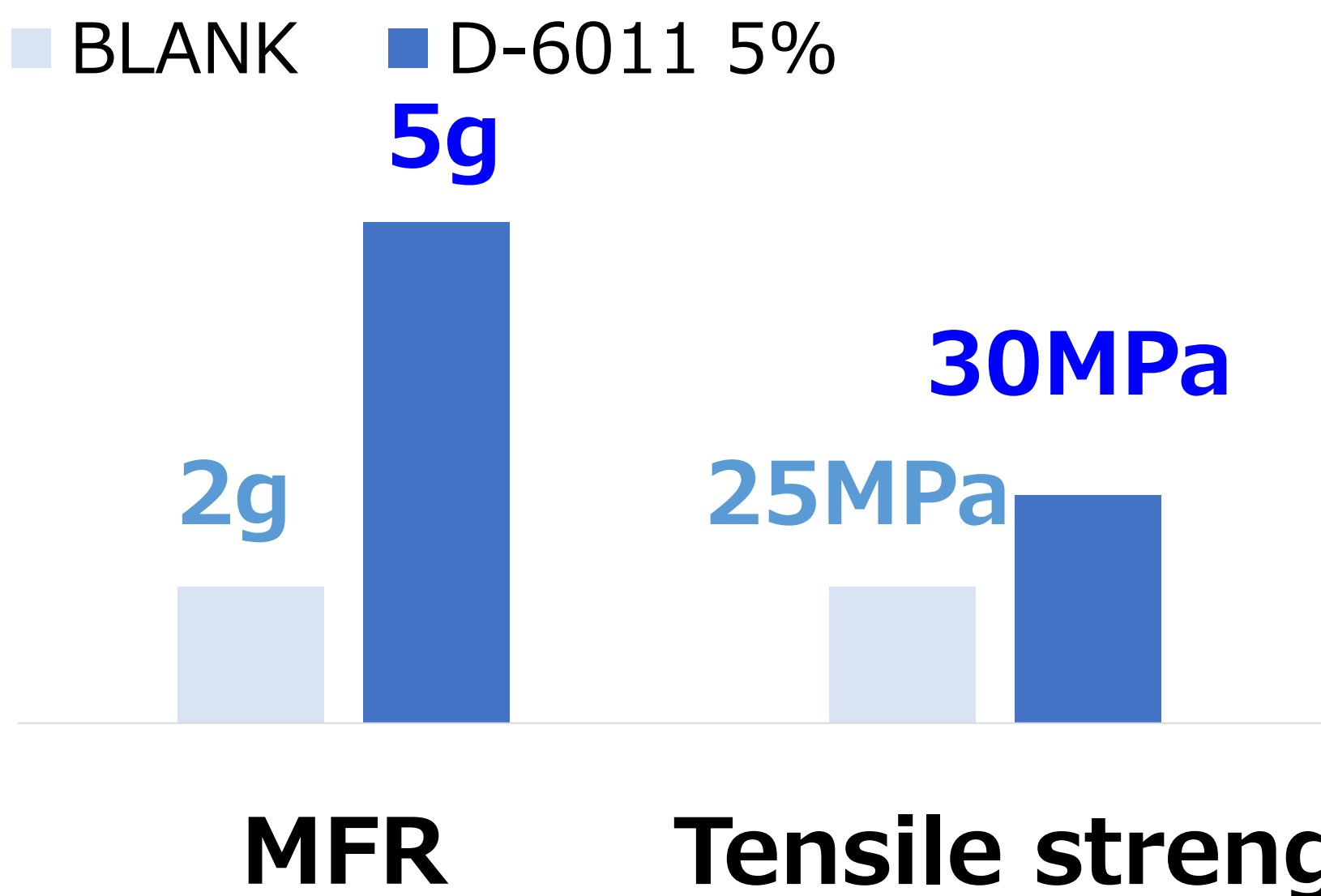


Effect

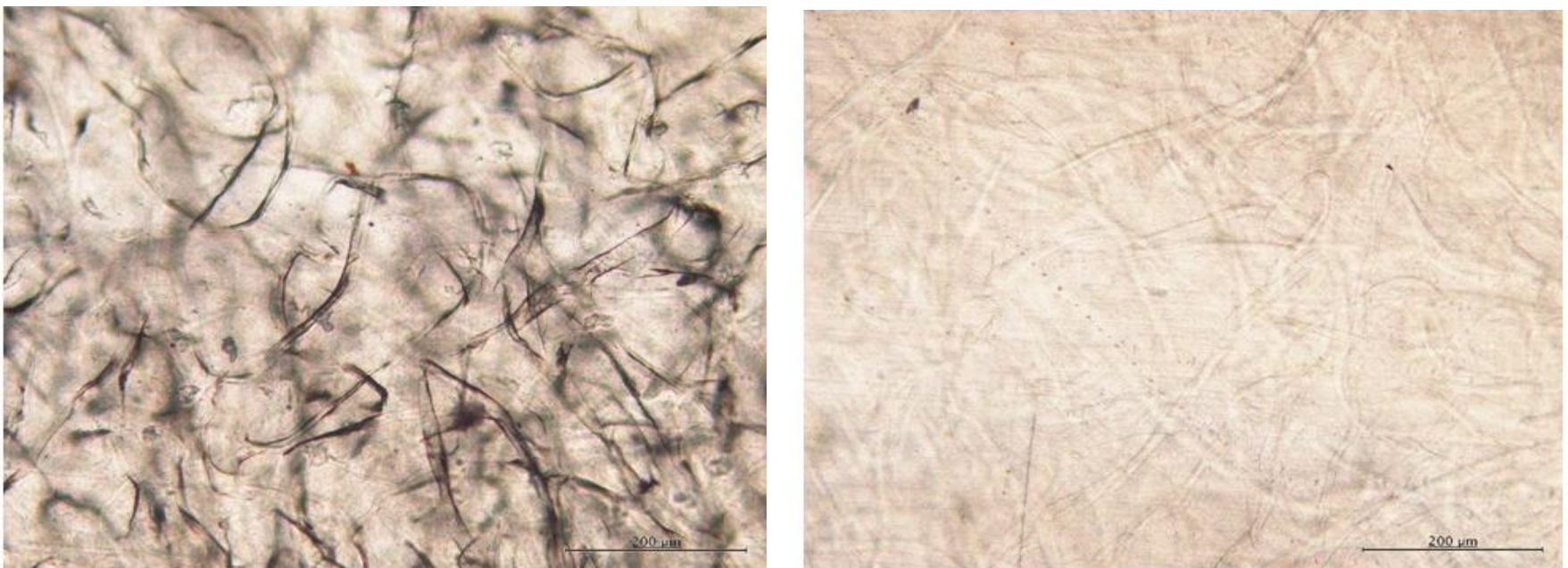
◆Effect on Adhesives



◆Effect on Resin/Filler Composites (Polyethylene/Cellulose)

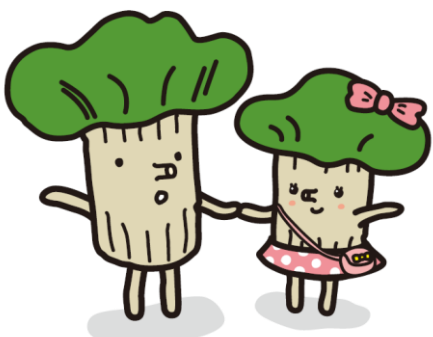


Optical microscope image



BLANK

D-6011 compound



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